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1763

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TRANSMITTAL FORM

(to be used for all correspondence after initial filing)

Application Number	10/677,639
Filing Date	October 2, 2003
First Named Inventor	Ian M. McMackin
Art Unit	1763
Examiner Name	Unassigned
Attorney Docket Number	PA74/JVC-02-01-03

Total Number of Pages in This Submission

ENCLOSURES *(Check all that apply)*

- ☐ Fee Transmittal Form
  - ☐ Fee Attached
- ☐ Amendment/Reply
  - ☐ After Final
  - ☐ Affidavits/declaration(s)
- ☐ Extension of Time Request
- ☐ Express Abandonment Request
- ☑ Information Disclosure Statement
- ☐ Certified Copy of Priority Document(s)
- ☐ Response to Missing Parts/ Incomplete Application
  - ☐ Response to Missing Parts under 37 CFR 1.52 or 1.53
- ☐ Drawing(s)
- ☐ Licensing-related Papers
- ☐ Petition
- ☐ Petition to Convert to a Provisional Application
- ☐ Power of Attorney, Revocation Change of Correspondence Address
- ☐ Terminal Disclaimer
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- ☐ CD, Number of CD(s) _____
- ☐ After Allowance communication to Technology Center (TC)
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- ☐ Appeal Communication to TC **(Appeal Notice, Brief, Reply Brief)**
- ☐ Proprietary Information
- ☐ Status Letter
- ☑ Other Enclosure(s) (please Identify below):
  Form 1449 - IDS
  Fifty-three (53) References
  Return Receipt Postcard to Kenneth Brooks

Remarks

SIGNATURE OF APPLICANT, ATTORNEY, OR AGENT

Firm or Individual name	Law Office of Kenneth C. Brooks
Signature	Kenneth Brooks
Date	2/23/04

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: McMackin et al. PATENT APPLICATION
Serial No.: 10/677,639 Group Art Unit: 1763
Filing Date: October 2, 2003 Examiner: Unassigned
For: Single Phase Fluid Imprint Lithography Method

INFORMATION DISCLOSURE STATEMENT

Commissioner
for Patents
Alexandria, VA 22313-1450

Sir:

The following information is submitted in compliance with Applicants' duty of disclosure under 37 C.F.R. § 1.56. Form PTO-1449 and a copy of each reference recited below accompanies this document. It is respectfully requested that the cited information be expressly considered during the prosecution of this application, and the references be made of record therein and appear among the "references cited" on any patent to issue therefrom.

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Patent Number	Inventor	Grant Date
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4,451,507	Beltz et al.	05/29/1984
4,544,572	Sandvig	10/01/1985
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5,480,047	Tanigawa et al.	01/02/1996
5,723,176	Keyworth et al.	03/03/1998
5,753,014	Van Rijn	05/19/1998
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6,309,580	Chou	10/20/2001
6,334,960	Willson et al.	01/01/2002
6,355,198	Kim et al.	03/12/2002
6,391,217	Schaffer et al.	05/21/2002

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09/976,681	Bailey et al.	10/12/2001
09/905,718	Willson et al.	05/16/2002
10/194,414	Sreenivasan et al.	07/11/2002

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Document No.	Inventor	Pub. Date
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Chou et al. "Imprint Lithography with Sub-10 nm Feature Size and High Throughput", *Microelectronic Engineering 35*, pp. 237-240, 1997.

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Chou, Stephen et al. "Lithographically-induced Self Assembly of Periodic Micropillar Arrays," *Journal of Vacuum Science and Technology*, vol. 17, pp. 3197-3202, 1999.

Choi, B.J. et al. "Design of Orientation Stages for Step and Flash Imprint Lithography," *Precision Engineering*, vol. 25, pp. 192-199, 2001.

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Nguyen, A. Q. "Asymmetric Fluid-Structure Dynamics in Nanoscale Imprint Lithography," University of Texas at Austin, August 2001.

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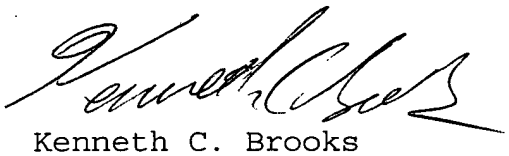

Kenneth C. Brooks
Reg. No. 38,393

P.O. Box 81536
Austin, Texas 78708-1536
Telephone: 512-527-0104
Facsimile: 512-527-0107
patentsrus@earthlink.net

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

Sheet 1 of 5

Complete if Known	
Application Number	10/677,639
Filing Date	10/2/2003
First Named Inventor	McMackin et al.
Group Art Unit	1763
Examiner Name	Unassigned
Attorney Docket Number	PA74/JVC-02-01-03

U.S. PATENT DOCUMENTS

Examiner Initials*	Cite No.[1]	U.S. Patent Document Number	Kind Code[2] (if known)	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
	A1	4,267,212		Sakawaki	05-12-1981	
	A2	4,451,507		Beltz et al.	05-29-1984	
	A3	4,544,572		Sandvig et al.	10-01-1985	
	A4	4,731,155		Napoli et al.	03-15-1988	
	A5	5,259,926		Kuwabara et al.	11-09-1993	
	A6	5,480,047		Tanigawa et al.	01-02-1996	
	A7	5,723,176		Keyworth et al.	03-03-1998	
	A8	5,753,014		Van Rijn	05-19-1998	
	A9	5,772,905		Chou	06-30-1998	
	A10	5,900,160		Whitesides et al.	05-04-1999	
	A11	5,912,049		Shirley	06-15-1999	
	A12	5,948,470		Harrison et al.	09-07-1999	
	A13	6,039,897		Lochhead et al.	03-21-2000	
	A14	6,128,085		Buermann et al.	10-03-2000	
	A15	6,143,412		Schueller et al.	11-07-2000	
	A16	6,168,845		Fontana, Jr. et al.	01-02-2001	
	A17	6,180,239		Whitesides et al.	01-30-2001	
	A18	6,218,316		Marsh	04-17-2001	
	A19	6,309,580		Chou	10-20-2001	
	A20	6,334,960		Willson et al.	01-01-2002	
	A21	6,355,198		Kim et al.	03-12-2002	
	A22	6,391,217		Schaffer et al.	05-21-2002	

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Sheet	2	of	5

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Filing Date	10/2/2003
First Named Inventor	McMackin et al.
Group Art Unit	1763
Examiner Name	Unassigned
Attorney Docket Number	PA74/JVC-02-01-03

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	A23	DE	2800476		Lamprecht et al.	07-13-1978		
	A24	JP	1-196749		Matsumoto et al.	08-08-1989		
	A25	WO	01/69317		Montelius et al.	09-20-2001		
	A26	WO	01/90816		Heidari	11-29-2001		

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Sheet 3 of 5

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Application Number	10/677,639
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First Named Inventor	McMackin et al.
Group Art Unit	1763
Examiner Name	Unassigned
Attorney Docket Number	PA74/JVC-02-01-03

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.[1]	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T[2]
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	A28	LIN, "Multi-Layer Resist Systems", Introduction of Microlithography," American Chemical Society, 1983, pp. 287-350, IBM T.J. Watson Research Center, Yorktown Heights, New York 10598.	
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	A30	KRUG et al., "Fine Patterning of Thin Sol-Gel Films," Journal of Non-Crystalline Solids, 1992, pp. 447-450, vol. 147 & 148.	
	A31	ANANTHASURESH et al., "Strategies for Systematic Synthesis of Compliant MEMS," ASME, DSC-vol. 55-2, Dynamic Systems and Control, 1994, pp. 677-686, vol. 2.	
	A32	Kotachi et al., "Si-Containing Positive Resist for ArF Excimer Laser Lithography," J. PhotopolymerSci. Tevhnol. 8(4) 615-622, 1995.	
	A33	Krauss et al., "Fabrication of Nanodevices Using Sub-25nm Imprint Lithography," Appl. Phys. Lett 67(21), 3114-3116, 1995	
	A34	CHOU et al., "Imprint of Sub-25 nm Vias and Trenches in Polymers," Applied Physics Letters, November 20, 1995, pp. 3114-3116, vol. 67(21).	
	A35	CHOU et al., "Imprint Lithography with 25-Nanometer Resolution," Science, Apr. 5, 1996, pp. 85-87, vol. 272.	
	A36	HAISMA et al., "Mold-Assisted Nanolithography: A Process for Reliable Pattern Replication," Journal of Vacuum Science and Technology, Nov/Dec 1996, pp. 4124-4128, vol. B 14(6).	
	A37	CHOU et al., "Imprint Lithography with Sub-10nm Feature Size and High Throughput," Microelectronic Engineering, 1997, pp. 237-240, vol. 35.	

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	A41	COLBURN. et al., "Step and Flash Imprint Lithography: A New Approach to High-Resolution Patterning", Proc. of SPIE, 1999, pp. 379-389, vol. 3676.	
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Examiner Initials*	Cite No.[1]	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T[2]
	A49	Nguyen, A. Q., "Asymmetric Fluid-Structure Dynamics in Nanoscale Imprint Lithography," University of Texas at Austin, August 2001.	
	A50	CHOI et al., "Flexture Based Macro Motion Translation Stage," U.S. Patent Application 09/934,248, Filed with USPTO on Auguts 21, 2001.	
	A51	BAILEY et al., "Template for Room Temperature Low Pressure Micro- and Nano-Imprint Lithography," U.S. Patent Application 09/976,681, Filed with USPTO on October 12, 2001.	
	A52	WILLSON et al., "Method and System for Fabricating Nanoscale Patterns in Light Curable Compositions Using an Electric Field," U.S. Patent Application 09/905,718, Filed with USPTO on May 16, 2002	
	A53	SREENIVASAN et al., "Step and Repeat Imprint Lithography Systems," U.S. Patent Application 10/194,414, Filed with USPTO July 11, 2002.	

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